EPIC Online Technology Meeting on Lithography

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Strategic Business Development
(Corporate Strategy & Marketing)

3rd July 2020

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Lithography systems for multiple markets

Our customers range from <7nm logic fabs to III-V photonic fabs

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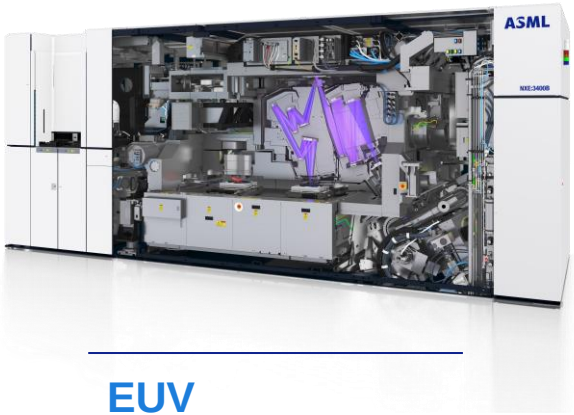

EUV

TWINSCAN NXE:3400C

Wavelength:	13.5 nm
Resolution:	13 nm
NA:	0.33
Overlay:	1.0 nm
Wafer size:	300 mm
Productivity:	170 wph

In the same way that 0.33NA enables 7nm and 5nm Logic, **0.55NA** EUV will be needed to enable 3nm Logic

Immersion

TWINSCAN NXT:2000i

Wavelength:	193 nm
Resolution:	≤ 38 nm
NA:	1.35
Overlay:	~1.5 nm
Wafer size:	300 mm
Productivity:	275 wph

State-of-the-art immersion systems, in high-volume manufacturing of the 7nm Logic and advanced DRAM nodes

Mature Products

Steppers & Scanners

Wavelength:	365 to 193 nm
Resolution:	400 to 90 nm
Overlay:	100 to 12 nm
Wafer size:	75 to 200 mm
Productivity:	100 - >200 wph

Emerging markets are taking advantage of the performance and productivity of our mature products

Our **holistic lithography** portfolio underpins our success

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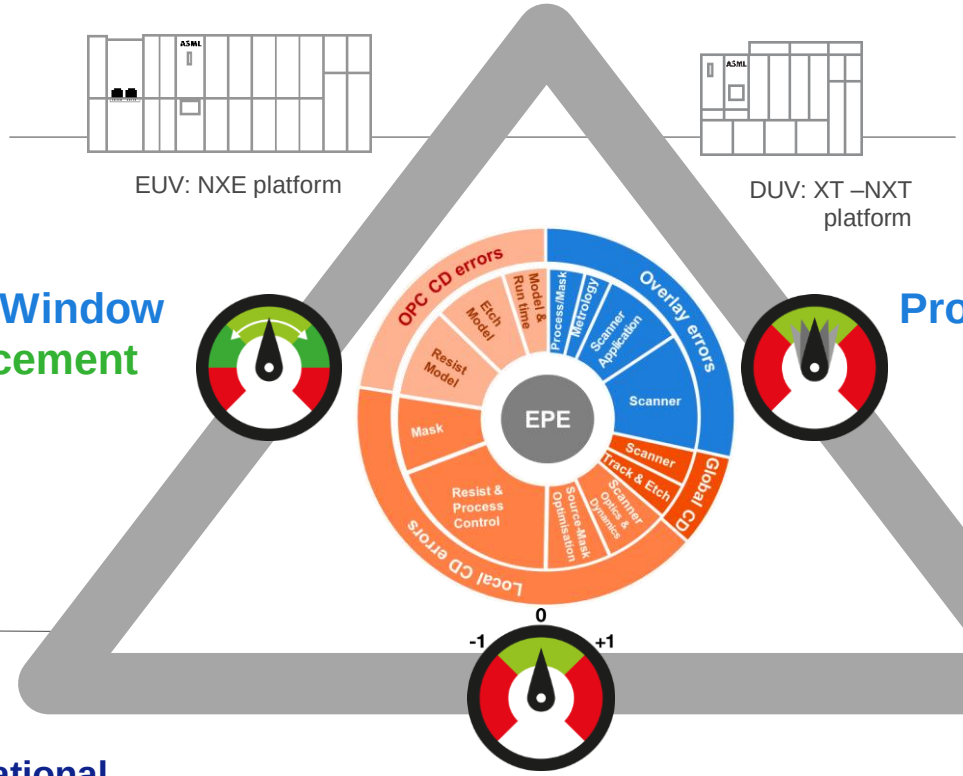
Lithography scanner with advanced control capability



2019 €11.8B - A record year

ASML sales grew by 8% despite an overall decline in our industry reflecting the increasing importance of lithography in the semiconductor industry

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€11.8bn

Revenue

Compelling market drivers

Major innovation drivers such as ***artificial intelligence***, ***5G***, ***high-performance computing***, ***autonomous driving and big data*** are enabling new end-user applications.

These applications require a larger number of high-performance ***Logic chips***, fueling demand for leading-edge nodes.

€2.0bn

R&D

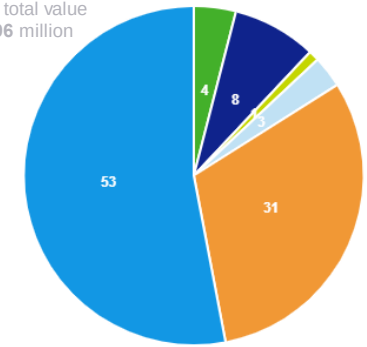
Investing in the future

Our focus is on bringing our current EUV technology to the maturity level of our DUV systems and developing the next-generation EUV technology: High-NA.

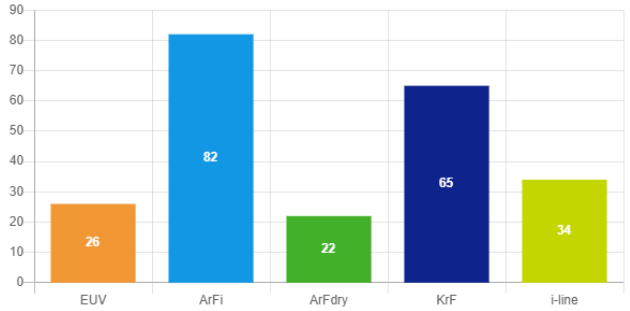
In addition to EUV developments, we continue to invest in our DUV technology and our Metrology & Inspection product portfolio.

Net system sales breakdown (% system sales)

2019 total value
€8,996 million



Sales of lithography systems (units)



Open Innovation from design to manufacturing

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